ELECTRONIC INFORMATION DISCLOSURE STATEMENT

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Title of Invention

ENDPOINT DETECTION IN CHEMICAL-MECHANICAL POLISHING OF PATTERNED WAFERS HAVING A LOW PATTERN DENSITY

Application Number:

10/707120

Confirmation Number:

First Named Applicant:

Xinhui Wang

Attorney Docket Number:

FIS920030031

Art Unit:

3723

Examiner:

Search string:

(6176765 or 6291351 or 6440263).pn

US Patent Documents

Note: Applicant is not required to submit a paper copy of cited US Patent Documents

init	Cite.No.	Patent No.	Date	Patentee	Kind	Class	Subclass
DVN	1	6176765	2001-01-23	Li et al.	1	-	
	2	6291351	2001-09-18	Li et al.			
V	3	6440263	2002-08-27	Li et al.			

Signature

Examiner Name	Date			
Dung vom hyngen	8-9-2004			